

03500.102994.

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)	
	:	Examiner: Not Yet Assigned
KAZUHIKO FUKUTANI, ET AL.	)	
	:	Group Art Unit: 1743
Application No.: 10/530,549	)	
	:	Confirmation No.: 7631
Filed: January 30, 2006	)	
	:	
For: FILED-EFFECT TRANSISTOR,	)	
SENSOR USING IT, AND	:	
PRODUCTION METHOD	)	
THEREOF	:	April 25, 2007

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed Form PTO-1449. Copies of the listed articles and foreign documents are also enclosed.

For the concise explanation of relevance of non-English document JPA 2001-261376, the Examiner is respectfully referred to the English abstract attached thereto.

Also, for the concise explanation of relevance of non-English document JPA 9-157062, the Examiner is respectfully referred to the English abstract attached thereto, and to the machine English translation of the foreign document as well.

It is respectfully requested that the above information be considered by the Examiner and that an initialed copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our address given below.

Respectfully submitted,

/John A. Krause/  
John A. Krause  
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NY\_MAIN630906v1

FORM PTO 1449 (modified)  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)				ATTY DOCKET NO. <b>03500.102994.</b>		APPLICATION NO. <b>10/530,549</b>	
				APPLICANT <b>KAZUHIKO FUKUTANI ET AL.</b>			
				FILING DATE <b>January 30, 2006</b>		GROUP <b>1743</b>	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		2005/0053773 A1	03/10/05	Fukutani et al.	428	209	
		2004/0043208 A1	03/04/04	Fukutani et al.	428	304.4	
		2004/0033339 A1	02/19/04	Fukutani et al.	428	137	
		6,602,620 B1	08/05/03	Kikitsu et al.	428	694 T	
		6,027,796	02/22/00	Kondoh et al.	428	312.8	
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
	JP	2001-261376	09/26/01	Japan			Abstract
	JP	9-157062	06/17/97	Japan			Abstract and English Translation
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
		C.D. Adams et al., "Monte Carlo Simulation of Phase Separation During Thin-Film Codeposition," J. Appl. Phys. 74 (3), 1 August 1993, American Institute of Physics, pp. 1707-1715.					
		C.D. Adams et al., "Transition from Lateral to Transverse Phase Separation During Film Co-deposition," Appl. Phys. Lett. 59 (20), 11 November 1991, American Institute of Physics, pp. 2535-2537.					
		C.D. Adams et al., "Phase Separation During Co-deposition of Al-Ge Thin Films," J. Mater. Res., Vol. 7, No. 3, March 1992, Materials Research Society, pp. 653-667					
		M. Atzmon et al., "Phase Separation During Film Growth," J. Appl. Phys. 42 (2), 15 July 1992, American Institute of Physics, pp. 442-446.					
		M. Jacobs et al., "Unbalanced Magnetron Sputtered Si-Al Coatings: Plasma Conditions and Film Properties Versus Sample Bias Voltage," Surface and Coatings Technology 116-119 (1999) pp. 735-741.					
EXAMINER				DATE CONSIDERED			

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 1 of 1